	Туре	L	#	Hits	Search Text	DBs	Time Stamp
1	BRS	L1		71	khoi near phan.in.	US- PGPUB; USPAT; EPO; JPO; DERWE NT; IBM_T DB	2004/12/2 2 19 <b>:</b> 50
2	BRS	L2		0	1 and (alignment near3 mark)	US- PGPUB; USPAT; EPO; JPO; DERWE NT; IBM_T DB	2004/12/2 2 19:52
3	BRS	L3		0	ragarajan near bharath.in.	US- PGPUB; USPAT; EPO; JPO; DERWE NT; IBM_T DB	2004/12/2 2 19:52

	Туре	L #	Hits	Search Text	DBs	Time Stamp
4	BRS	L4	11/11	rangarajan near bharath.in.	US- PGPUB; USPAT; EPO; JPO; DERWE NT; IBM_T DB	2004/12/2 2 19:52
5	BRS	L5	4	4 and (alignment near3 mark)	IH P() •	2004/12/2 2 19:54
6	BRS	L6	215	singh near bhanwar.in.	US- PGPUB ; USPAT ;	2004/12/2 2 19:54

	Туре	L	#	Hits	Search Text	DBs	Time Stamp
7	BRS	L7		2	6 and (alignment near3 mark)	IH. P( ) •	2004/12/2 2 19:54
8	BRS	L8		597	438/462.ccls.	US- PGPUB ; USPAT ;	2004/12/2 2 19:54
9	BRS	L9		117/	8 and (alignment near3 mark)	US- PGPUB ; USPAT ;	2004/12/2 2 19:55

	Type	L #	Hits	Search Text	DBs	Time Stamp
10	BRS	L10	51	8 and (second near3 alignment near3 mark)	US- PGPUB; USPAT; EPO; JPO; DERWE NT; IBM_T DB	2004/12/2 2 19:55
11	BRS	L11	0	8 and (second near3 alignment near3 mark) near25 (diagonal)	US- PGPUB; USPAT; EPO; JPO; DERWE NT; IBM_T DB	2004/12/2 2 19:56
12	BRS	L12	4	(second near3 alignment near3 mark) near25 (diagonal)	US- PGPUB; USPAT; EPO; JPO; DERWE NT; IBM_T DB	2004/12/2 2 19:58

	Туре	L #	Hits	Search Text	DBs	Time Stamp
13	BRS	L13	75	(alignment near3 mark) near25 (diagonal)	US- PGPUB; USPAT; EPO; JPO; DERWE NT; IBM_T DB	2004/12/2 2 19:58
14	BRS	L14	9	((alignment near3 mark) near25 (diagonal)) same (reticle)	US- PGPUB; USPAT; EPO; JPO; DERWE NT; IBM_T DB	2004/12/2 2 20:04
15	BRS	L15	15	((marks) near25 (diagonal)) same (reticle)	US- PGPUB ; USPAT	2004/12/2 2 20:04

	Туре	L #	Hits	Search Text	DBs	Time Stamp
16	BRS	L16	5	((marks) near25 (diagonal near3 line\$1)) same (reticle)	US- PGPUB; USPAT; EPO; JPO; DERWE NT; IBM_T DB	2004/12/2 2 20:16
17	BRS	L17	5	((marks) near25 (diagonal near3 line\$1)) near25 (reticle)	US- PGPUB; USPAT; EPO; JPO; DERWE NT; IBM_T DB	2004/12/2 2 20:16
18	BRS	L18	4	((marks) near15 (diagonal near3 line\$1)) near25 (reticle)	US- PGPUB ; USPAT	2004/12/2 2 20:16

	Туре	L #	Hits	Search Text	DBs	Time Stamp
19	BRS	L19	4	((marks) near15 (diagonal near line\$1)) near25 (reticle)	1H' D( ) •	2004/12/2 2 20:17
20	BRS	L20	436	((marks) near15 (diagonal or line\$1)) near25 (reticle)	US- PGPUB ; USPAT	2004/12/2 2 20:17
21	BRS	L21		((marks) near15 (diagonal or line\$1)) near15 (intersect\$3) near25 (reticle)	US- PGPUB; USPAT; EPO; JPO; DERWE NT; IBM_T DB	2004/12/2 2 20:32

	Туре	L #	Hits	Search Text	DBs	Time Stamp
22	BRS	L22	4	((marks) near15 (diagonal near5 line\$1)) near25 (reticle)	US- PGPUB; USPAT; EPO; JPO; DERWE NT; IBM_T DB	2004/12/2 2 20:41
23	BRS	L23	0	((overlay) near15 (diagonal near5 line\$1)) near25 (reticle)	US- PGPUB; USPAT; EPO; JPO; DERWE NT; IBM_T DB	2004/12/2 2 20:39
24	BRS	L24	11 1	((overlay or target) near15 (diagonal near5 line\$1)) near25 (reticle)	US- PGPUB ; USPAT	2004/12/2 2 20:39

	Туре	L #	Hits	Search Text	DBs	Time Stamp
25	BRS	L25	0	((overlay or target) near35 (diagonal near5 line\$1)) near25 (reticle)	LPO; JPO; DERWE NT; IBM_T	2004/12/2 2 20:39
26	BRS	L26	205	((marks) near15 (diagonal near line\$1))	IH: P() •	2004/12/2 2 20:41
27	BRS	L27	0	((marks) near15 (diagonal near line\$1)) near25 (processor)	US- PGPUB ; USPAT	2004/12/2 2 20:41

	Туре	L #	Hits	Search Text	DBs	Time Stamp
28	BRS	L28	0	((marks) near15 (diagonal near line\$1)) same (processor)	US- PGPUB; USPAT; EPO; JPO; DERWE NT; IBM_T DB	2004/12/2 2 20:42
29	BRS	L29	32	((marks) near15	US- PGPUB; USPAT; EPO; JPO; DERWE NT; IBM_T DB	2004/12/2 2 21:18
30	BRS	L30	0	((marks) near15 (additional near5 diagonal near line\$1)) and (processor)	US- PGPUB; USPAT; EPO; JPO; DERWE NT; IBM_T DB	2004/12/2 2 21:15

	Туре	L #	Hits	Search Text	DBs	Time Stamp
31	BRS	L31	0		US- PGPUB; USPAT; EPO; JPO; DERWE NT; IBM_T DB	2004/12/2 2 21:15
32	BRS	L32	58	((additional near5 diagonal near line\$1))	US- PGPUB; USPAT; EPO; JPO; DERWE NT; IBM_T DB	2004/12/2 2 21:15
33	BRS	L33	0	same (mark\$1)	US- PGPUB ; USPAT	2004/12/2 2 21:15

	Туре	L #	Hits	Search Text	DBs	Time Stamp
34	BRS .	L34	58	((additional near5 diagonal near line\$1))	US- PGPUB; USPAT; EPO; JPO; DERWE NT; IBM_T DB	2004/12/2 2 21:16
35	BRS	L35	10	((additional near diagonal near line\$1))	US- PGPUB ; USPAT	2004/12/2 2 21:16
36	BRS	L36	39	((marks) near15 (diagonal near5 line\$1)) and (processor)	US- PGPUB ; USPAT	2004/12/2 2 21:19

	Туре	L #	Hits	Search Text	DBs	Time Stamp
37	BRS	L37	0	((marks) near15 (diagonal near5 line\$1)) and (x near initiative)	IH D( ) •	2004/12/2 2 21:19
38	BRS	L38	1	((marks) near15 (diagonal near5 line\$1)) and (initiative)	IH D( ) *	2004/12/2 2 21:19
39	BRS	L40	1/1	((marks or alignment) near15 (diagonal near5 line\$1)) same (reticle)	US- PGPUB; USPAT; EPO; JPO; DERWE NT; IBM_T DB	2004/12/2 2 21 <b>:</b> 20

	Туре	L #	Hits	Search Text	DBs	Time Stamp
40	BRS	L41	3	((marks or alignment) near15 (diagonal near5 line\$1)) same (processor)	US- PGPUB; USPAT; EPO; JPO; DERWE NT; IBM_T DB	2004/12/2 2 21:21
41	BRS	L39	413	((marks or alignment) near15 (diagonal near5 line\$1))	US- PGPUB ; USPAT ;	2004/12/2 2 21:28
42	BRS	L42	28	((marks or alignment) near15 (diagonal near5 line\$1)) near45 (reticle or detect\$3)	US- PGPUB ; USPAT	2004/12/2 2 21:35

	Туре	L #	Hits	Search Text	DBs	Time Stamp
43	BRS	L43	388		US- PGPUB; USPAT; EPO; JPO; DERWE NT; IBM_T DB	2004/12/2 2 21:41
44	BRS	L44	175	(reticle)	US- PGPUB; USPAT; EPO; JPO; DERWE NT; IBM_T DB	2004/12/2 2 21:36
45	BRS	L45	II / ¬ ¤ n	(reticle)	US- PGPUB ; USPAT	2004/12/2 2 21:42

	Туре	L #	Hits	Search Text	DBs	Time Stamp
46	BRS	L46		((marks near alignment) or (dot\$1) or (pattern\$1)) near10 (diagonal) near15 (reticle)	(H: P( ) •	2004/12/2 2 21:42

	U	1	Document ID	Title	Current OR
1			US 20040218158 A1	Exposure method and device	355/30
2		i	US 6765647 B1	Exposure method and device	355/55
3			US 6498352 B1	Method of exposing and apparatus therefor	250/548
4			US 6279881 B1	Method and apparatus which exposes a second object with a pattern formed on a first object	250/548
5			US 6051843 A	Exposure apparatus and method which synchronously moves the mask and the substrate to measure displacement	250/548
6			US 5844247 A	mask and the substrate to measure displacement	250/548
7	<u> </u>		US 5695897 A	Alignment method and semiconductor exposure method	430/22

	ប	1	Document II	Title	Current OR
8			US 5646413 <i>I</i>	Exposure apparatus and method which synchronously moves the mask and the substrate to measure displacement	250/548
9	X		JP 63291431 A	SEMICONDUCTOR DEVICE	